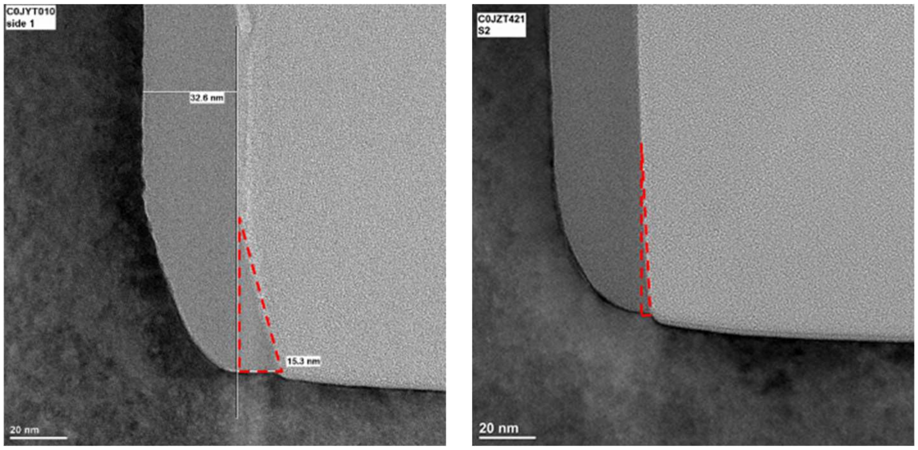

Figure 1. Reduced spacer footing: (left) typical etch process (right) process with proposed novel etch gas.

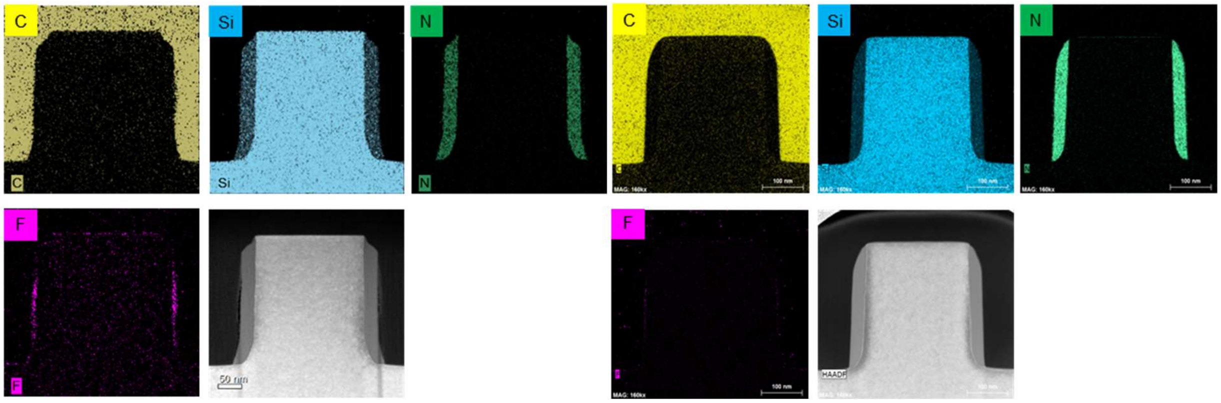

Figure 2. Minimal chemical residual/damage: left) typical etch process (right) process with proposed novel etch gas.

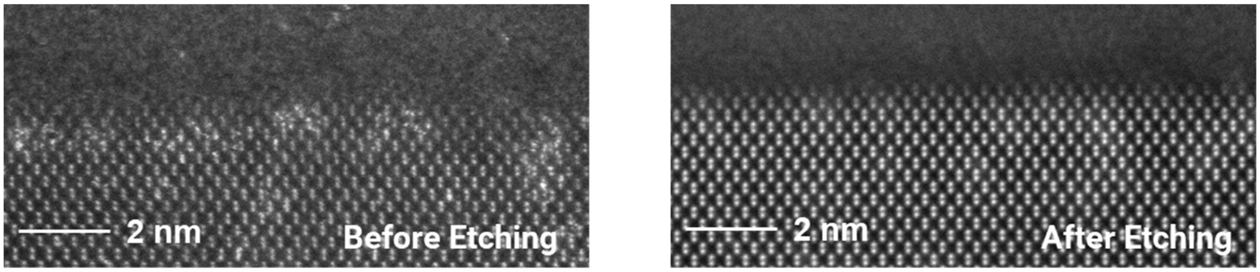

Figure 3. Surface smoothing effect after ALE with proposed novel etch gas.